

# Agenda Highlights—

*What new you can expect to learn in the 2020 Source Workshop*

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The 2020 Source Workshop is around the corner, October 31- November 5. The workshop that started as a two-day event ten years ago, will now be spread over six days virtually due to Covid-19. However, coming together virtually from your home office, is a benefit. We have added two days of short courses and shortened the daily times to best accommodate attendees from Europe, US and Asia.

As EUV sources for current EUVL scanners are maturing, focus is now on metrology sources for EUVL, power scaling for scanner sources and sources for potential extension of EUVL via shorter wavelength sources or Blue-X. The 2020 Source Workshop agenda's keynote and invited talks on these topics will be invaluable. We are also offering a new course on EUV Sources which will include Fundamentals of EUV physics, Physics of EUV and Short Wavelength Sources with Focus on Atomic Physics and an overview of commercial EUV sources.

This year's keynote talks from Larissa Juschkina of KLA on source requirements for mask inspection and Steve Carson of Intel will talk on evolving source demands and requirements are sure to be informative. There will be a paper with experimental results from ARCNL on performance of 2 microns drive lasers for Sn LPP. I am very happy to have experimental results on this topic as they are a potential alternative to CO<sub>2</sub> lasers for power scaling and Blue-X. There are several papers with latest research on the working of Sn LPP from ARCNL, Utsunomia University, Gigaphoton and others.

We have an entire day devoted to code- comparison workshop this year, where various groups will present their modeling results for set of three simple problems related to Sn LPP sources. Comparison will allow us to dig deeper on how various models work, with end goal of increasing our understanding of physics of sources as well as improving the source. In addition, we have excellent papers on short wavelength sources, metrology sources and applications. Poster papers this year have been converted into "speed presentations" and posters themselves will be published on the website before the start of the meeting, to allow audience to view before the presentation. All in all, an incredible agenda, and we look forward to your participation. Register and review the workshop agenda, abstract book and short course descriptions at [www.euvlitho.com](http://www.euvlitho.com).



